

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Tomoyuki MATSUYAMA, Toru KIUCHI, Hiroshi CHIBA and Kazuyuki KATO

Application No.: Rule 53(b) Continuation of 09/487,996 filed January 20, 2000

Filed: February 7, 2002

Docket No.: 105218.01

For: METHOD FOR MANUFACTURING EXPOSURE APPARATUS AND METHOD
FOR MANUFACTURING MICRODEVICE

PRELIMINARY AMENDMENT

Director of the U.S. Patent and Trademark Office
Washington, D. C. 20231

Sir:

Prior to initial examination of this application, please amend the above-identified application as follows:

IN THE ABSTRACT:

Please replace the Abstract with the substitute Abstract attached hereto.

IN THE CLAIMS:

Please replace claims 1, 3 and 25 as follows:

1. (Amended) A method for manufacturing an exposure apparatus comprising the steps of:
- a providing step for providing a projection system projecting and exposing an image of a predetermined pattern formed on a reticle to a photosensitive substrate;
- a setting step for setting a correction member correcting residual aberration in said projection system at a predetermined position in an optical path between a reticle setting

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